
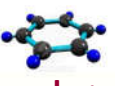
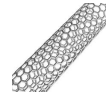

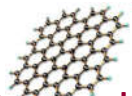

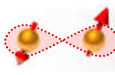
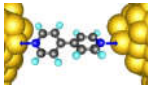

Nanoelectronics – Department of Physics


Spintronics

Quantumelectronics

Molecular electronics

**Experimental techniques**

---

E-beam lithography

Ultra low T


MCBJ technique

Pontcontact & Andreev spectroscopy

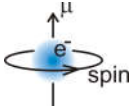
Electron spin resonance

Magneto-optics

## Motivation



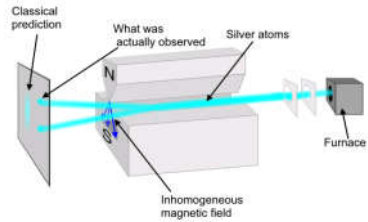
Spin: intrinsic degree of freedom



$$\mu_z = -2 \frac{\hbar e}{2m} \sigma_z = -2\mu_B \sigma_z \quad \text{with} \quad \sigma_z = \pm \frac{1}{2}$$

Early studies: Dirac equation ➔ series expansion in the nonrelativistic limit

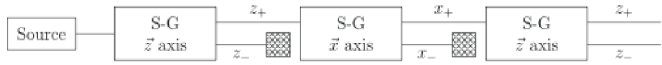
Stern-Gerlach experiment



$$H = H_0 - g\mu_B \vec{\sigma} \vec{B} + \frac{\hbar}{4m^2 c^2} \frac{\partial V_{at}}{\partial r} \vec{p} \vec{\sigma}$$

Spin-magnetic field interaction      Spin-orbit interaction

The true quantummechanical nature of the electronspin is demonstrated.



# Giant Magnetoresistance

**Prototype of spintronic devices**

Thus:  $R_{\uparrow\uparrow} < R_{\uparrow\downarrow}$

**Limits of easy model:**

- why only nano?
- role of material parameters
- microscopic description

role of the nonmagnetic spacer:  
no direct exchange between FM layers

Basic model: two separated current channels for spin up and spin down

Minority spin carriers are scattered due to reduced DOS

Result: increase of resistance for that channel

One layer is denoted free layer, and can be flipped

Direct electrical measurement of the magnetic state!

**device engineering:**

- coercive fields
- FM materials
- FM layer thicknesses
- spacer thickness (RKKY interaction)

J. F. Gregg, et al, J. Phys. D 35, 121 (2002)

# Spin injection and detection

**Optical pumping/orientation (semiconductors)**

incident circularly polarized light

due to selection rules the intensity ratio is:

$$\frac{I_{-3/2 \rightarrow -1/2}}{I_{-1/2 \rightarrow +1/2}} = \frac{\left| \langle -3/2, 3/2 | Y_1^1 | 1/2, -1/2 \rangle \right|^2}{\left| \langle -1/2, 3/2 | Y_1^1 | 1/2, +1/2 \rangle \right|^2} = 3$$

max. value

$$P_{cond} = \frac{n_{\uparrow} - n_{\downarrow}}{n_{\uparrow} + n_{\downarrow}} \geq \frac{-3+1}{3+1} = -\frac{1}{2}$$

after pumping, CB charge carriers are recombined and their spin lost

**Electron spin resonance:**

classical spin precession model:  
constant field in z direction, and oscillating field in the x,y plane

Resonant condition:  $\hbar\omega_0 = g\mu_B H$

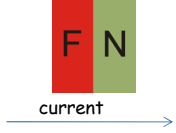
usually H is swept as the microwave lines are tuned to a specific frequency

$T_1$  (spin relaxation time)  
 $T_2$  (spin dephasing time)

I. Zutic et al, Rev. Mod. Phys, 76, 323 (2004)

## Spin injection and detection

**FM-NM interface**

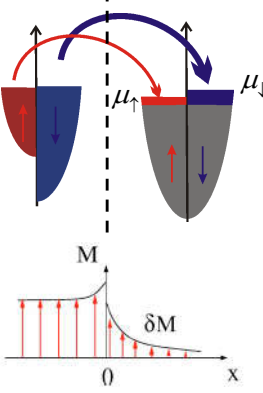


current →

Proper handling is the Valet-Fert model, i. e. Boltzmann equation for two subbands

very low efficiency for semiconductors

OK for metals and graphene



interface spin loss  $\delta_{F/N}$

spin imbalance of the current results in a different chemical potential for the two subbands, which decays in bulk

This is detected in the GMR experiment

diffusive spin transport

associated lifetime  $\tau_s$  and length scale  $l_s$

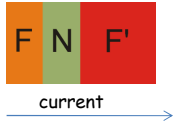
$l_s = \sqrt{D \tau_s}$  with  $\tau_m \ll \tau_s$

$D = \frac{1}{3} v_F l_m$

J. Bass and W. P. Pratt Jr, J. Phys.: Condens. Matter 19, 183201 (2007)

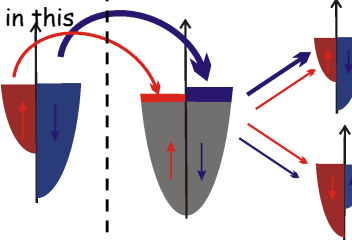
## Spin injection and detection

how to measure spin dephasing in this geometry?



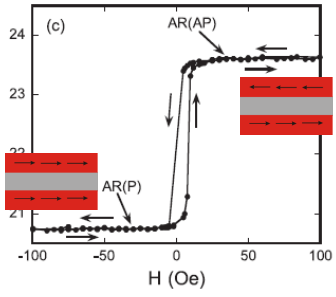
current →

the F layers have different coercive fields (e.g. different layer thickness)

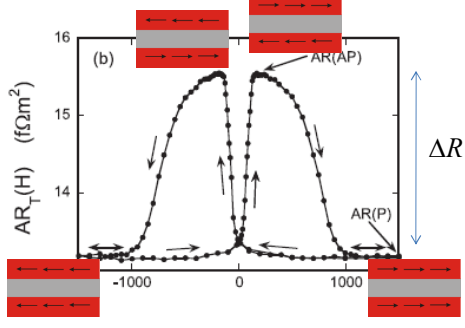


parallel: large current

antiparallel: suppressed current



(c)



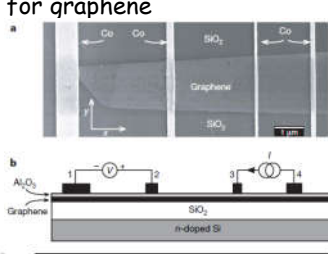
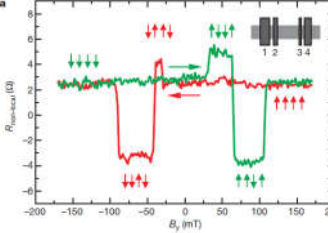
(b)

$\Delta R$

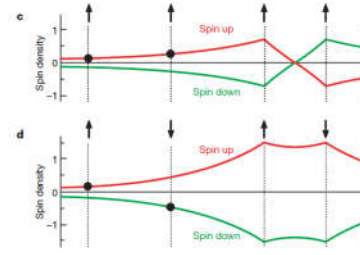
J. Bass and W. P. Pratt Jr, J. Phys.: Condens. Matter 19, 183201 (2007)

# Spin injection and detection

**Nonlocal measurements for graphene**

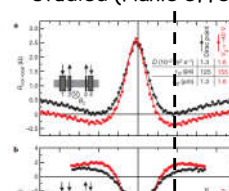



spin diffusion length is estimated to be  $2\mu\text{m}$



4 terminal device voltage terminals measure the chemical potential of the corresponding subband

in a small perpendicular B, precession was also studied (Hanle effect)



in principle: oscillatory behavior

limitations: spin dephasing, diffusive transport

rotation of  $180^\circ$

N. Tombros et al, Nature, 448, 571 (2007)

# Spin relaxation models

**Elliott-Yafett model**

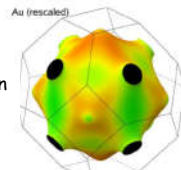
based on the spin-orbit interaction change in the momentum, i.e. scattering changes the spin state, too

$$V_{SO} = \frac{\hbar}{4m^2c^2} \frac{\partial V_{at}}{\partial r} \vec{p} \vec{\sigma}$$

prediction:  $\tau_s = |b|^2 \tau_m$  with  $|b|^2 \sim 10^{-5} \dots 10^{-3}$

material dependent constant

actually, worse than that. It even has a distribution on the Fermi surface

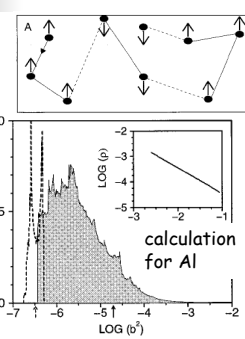


calculation for Au

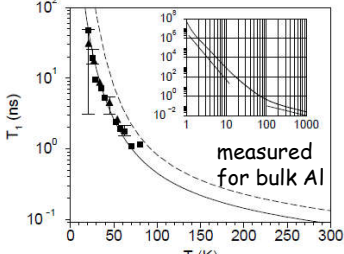
The spin-flip time scales with the transport lifetime temp. dependence: Bloch-Grüneisen law

for the spin diffusion length:

$$l_s = \sqrt{D \tau_s} \text{ with } D = \frac{1}{3} v_F l_m \Rightarrow l_s(T) \sim \tau_m(T)$$



calculation for Al



measured for bulk Al

J. Fabian and S.D. Darma, J. Vac. Sci. Tech. B, 17, 1708 (1999) J. Fabian and S.D. Darma, J. Appl. Phys, 85, 5075 (1999)  
 J. Fabian and S.D. Darma, Phys. Rev. Letters, 83, 1211 (1999) M. Gradhand, et al, Phys. Rev. B, 80, 224413 (2009)

# Spin relaxation models

**D'yakonov -Perel model**

If no inversion symmetry exists  
bulk: zinc-blende structure GaAs, ZnSe  
in thin layers due to confinement  
(see in *Semiconductor nanostructures*)

$E_{k↑} = E_{k↓}$       only  $E_{k↑} = E_{-k↓}$   
dictated by the  
Kramers theorem  
for spin  
diffusion length:

similar to Zeeman splitting

↓

effective  $\vec{B}(\vec{k})$   
magnetic field resulting in  
precession during propagation.  
When scattered, the spins starts  
precessing in another random  
direction

A random walk in the  
rotational angle space

$\langle \alpha^2 \rangle(t) = n \delta \alpha = \frac{t}{\tau_m} (\omega \tau_m)^2$   
 $\langle \alpha^2 \rangle(\tau_s) \approx 1$   
 $\tau_s \sim \tau_m^{-1}$   
diffusion length:  $\ell_s = \sqrt{D \tau_s}$   
no temp. dependence!

J. Fabian and S.D. Darma, J. Vac. Sci. Tech. B, 17, 1708 (1999)

# Spin Transfer Torque

previously: versatile devices, but  
external magnetic field is necessary to  
alter spin states. All electric control  
would be better.

free layer  
spin polarized  
current

**F N F'**

The free layer is rotated by  
the current instead of the  
external magnetic field. The  
shapes are however similar.

Potential application: memory cell

write: STT with high current pulse  
read: GMR/TMR at low current

word line      bit line

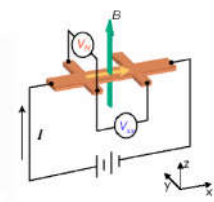
"1"      "0"

Current density:  $10^9 \text{ A/cm}^2$   
Only feasible in nano!

D. C. Ralph and M. D. Stiles, J. of Magn. Mag. Mater. 320, 1190 (2007)

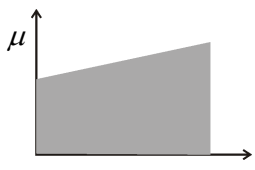
# Spin Hall effect

**Ordinary Hall effect:**  
classical model: due to Lorentz force, electrons carrying the current get deflected

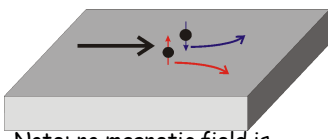


$$R_H = \frac{E_y}{j_x B_z} \text{ with } R_H = -\frac{1}{ne}$$

The result is a net electric field in the y direction



If spin-orbit coupling present, momentum scattering becomes anisotropic for each subband



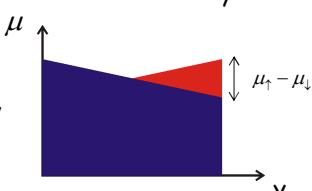
Note: no magnetic field is present!  
The generated spin polarization is out-of-plane:  $\vec{m} \sim \vec{k}_i \times \vec{k}_f$

No net voltage, only magnetization is visible at the edges

$$V_{SO} = \frac{\hbar}{4m^2 c^2} \frac{\partial V_{af}}{\partial r} \vec{p} \vec{\sigma}$$

$$m \approx g \mu_B \frac{\partial \rho}{\partial \varepsilon} (\mu_{\uparrow} - \mu_{\downarrow})$$

the device size is limited  $l_m < L_y \ll l_s$

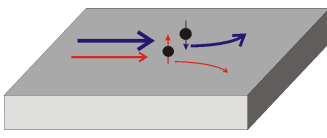


For realistic parameters ( $A_l, 10^6 \text{ A/cm}^2$ ), a small effect is predicted  
 $\mu_{\uparrow} - \mu_{\downarrow} \approx 10 \text{ neV}$

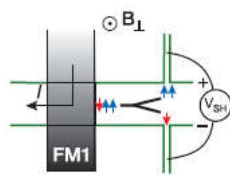
J. E. Hirsch, Phys. Rev. Letters, 83, 1834 (1999)

# Spin Hall effect

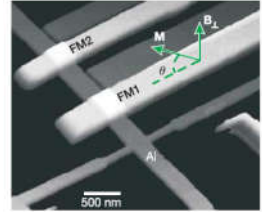
**How to measure it?**  
Idea: if the incident current is already spin polarized, then a measurable voltage develops



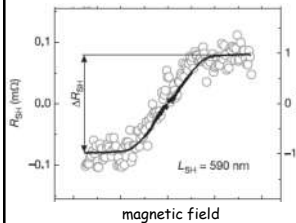
In actual nonlocal experiments, there is no net current through the device, however, the spin imbalance develops

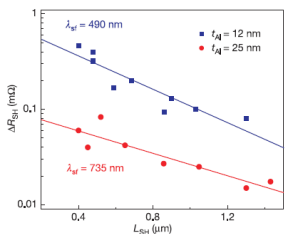


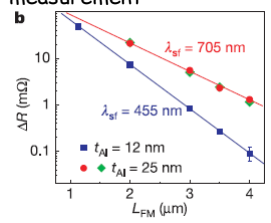
Out-of-plane magnetic field is necessary to have such magnetization to generate a signal



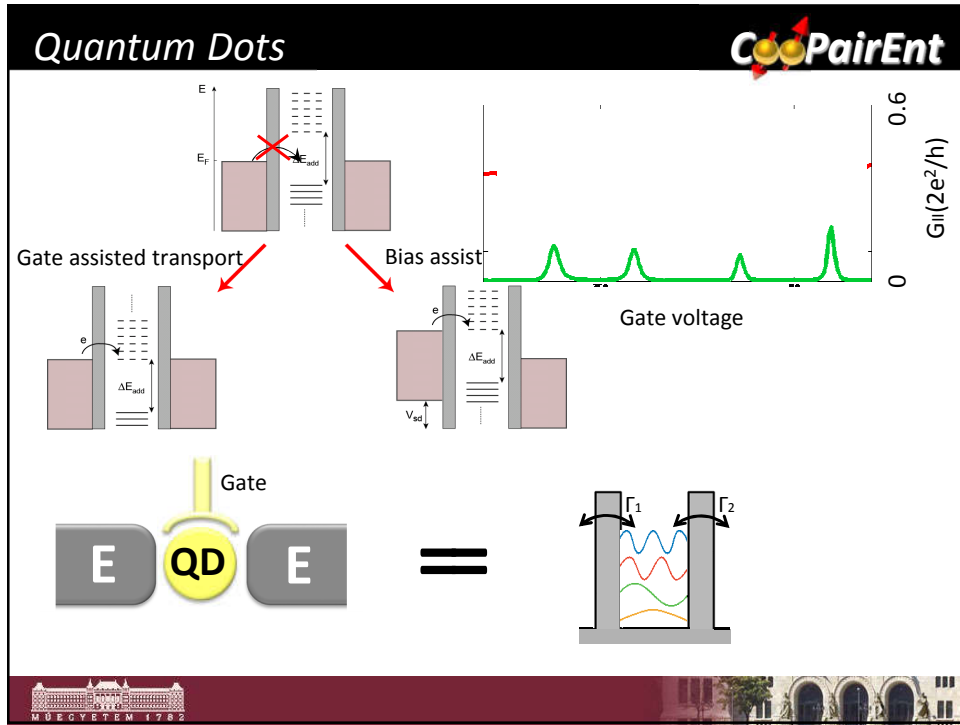
the device is characterized using FM2 in a standard nonlocal measurement







S. O. Valenzuela and M. Tinkham, Nature, 442, 176 (2006)



### Quantumelectronics

**MosFET: Bottleneck is leakage**

**Nanoscale objects:**  
 If  $L \approx \lambda_F$  or  $L \approx \lambda_\phi$  various quantum effects....


**Quantum electronics:**  
 Beside understand quantum effects the goal is to

- create well defined quantum subsystems,
- control and manipulate them

**Take the advantage of QUANTUM!**

## Principles: Qubit CoolPairEnt

**1959, '82 Feynman**  
*"When we get to the very, very small world... We can manufacture in different ways. We can use, not just circuits, but some system involving the quantized energy levels, or the interactions of quantized spins, etc."*

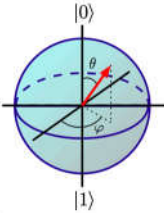



**Bit**  
Represent information today

0 or 1


**Quantum Bit (Qubit)**  
Represent information by two quantum states

$$|\psi\rangle = a|0\rangle + b|1\rangle$$






Vandersypsen, arXiv:0205193v1 (2002)




## Principles: Nonlocality, entanglement CoolPairEnt


**Quantum Bit**       $|\psi\rangle = a|0\rangle + b|1\rangle$


**Multiple Qubits**       $|\psi\rangle = |\psi\rangle_1 \otimes |\psi\rangle_2$



$|\psi\rangle = b|01\rangle + c|10\rangle$ 



 $P_{|1\rangle}^1$  Projection Qubit 1 to  $|1\rangle$


**f is a quantum gate**  
 $a|f(00)\rangle + b|f(01)\rangle + c|f(10)\rangle + d|f(11)\rangle$


  
 $|1,0\rangle$


**Quantum parallelism:** parallel evaluations grow exponentially with the number of Qubits ( $\approx 2^n$ )

**Nonlocality:** manipulation of QBit1 has consequence on QBit2



**Quantum computation**

**&**

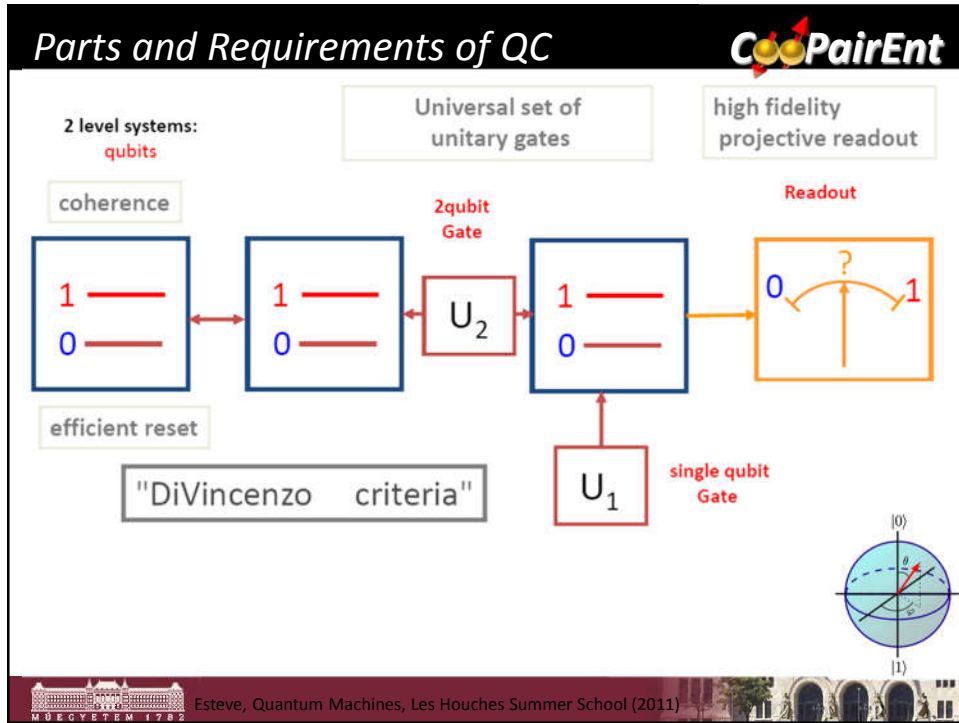
**communication**




Vandersypsen, arXiv:0205193v1 (2002)







### Technologies CoolPairEnt

Quantum systems with control and manipulation possibility

- Photons
- Cavity QED
- Trapped ions
- Superconductors
- NMR
- Quantum dots
- ...

In situ Error corrections!!!

Technology Roadmaps:  
 US <http://qist.lanl.gov/>,  
 EU <http://qist.ect.it/Reports/>

Blatt Quantum Machines, Les Houches Summer School (2011)

## Spin Qubits CoopairEnt

- **Qubit:**  
 $\frac{1}{2}$  spin of single electron trapped into a confinement potential, Scalable system
- **Initialization** of Qubits  
 e.g. by B field
- **Single Qubit and Two-Qubit gates**  
 by EDSR  $T \approx 150\text{ns}$  (2DEG) -  $20\text{ns}$  (NW)  
 based on exchange int.  $T \approx 200\text{ps}$
- **Readout**  
 Pauli-spin blockade (fidelity  $> 90\%$ )
- **Small decoherence**  
 $T_2 \approx 10\text{ns}$ ,  $T_2^* \approx 1\mu\text{s}$   
 Limited by hyperfine interaction

R. Hanson, Rev Mod Phys, 79, 1217 (2007)

## Spin Qubits, Various Material systems CoopairEnt

- **Qubit:**  
 $\frac{1}{2}$  spin of single electron trapped into a confinement potential, Scalable system
- **Initialization** of Qubits
- **Single Qubit and Two-Qubit gates**
- **Readout**
- **Small decoherence**

- Nuclear spin free system: C, Si/Ge
- Nuclear polarization
- Faster operation: Singlet-Triplet Qubit
- Topologic protection
- ...

R. Hanson, Rev Mod Phys, 79, 1217 (2007)

### Mobile entangled electrons

**CoopPairEnt**

1D architecture: interaction only between neighboring qubits  
 → Mobile entangled electrons help

MŰEGYETEM 1782 R. Hanson, Rev Mod Phys, 79, 1217 (2007)

### Cooper pair splitter

**CoopPairEnt**

Use Quantum Dots to reduce direct pair tunneling

$$\Psi = [\Psi_1(1)\Psi_2(2) + \Psi_2(1)\Psi_1(2)] \otimes (|\uparrow, \downarrow\rangle - |\downarrow, \uparrow\rangle)$$

MŰEGYETEM 1782 P. Recher et al., PRB (2002)

## Atomic scale switches - Memristors



### Introduction

- What is a *memristor*? How does it work?
- Applications
- Technology requirements against *real* memory devices

### The Ag<sub>2</sub>S system

- Experimental technique

### Other systems

- Valence change mechanism and versatile switching characteristics in Nb<sub>2</sub>O<sub>5</sub>

### New directions

- Artificial neural networks

## A possible realization of resistive switching

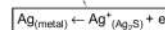
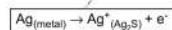
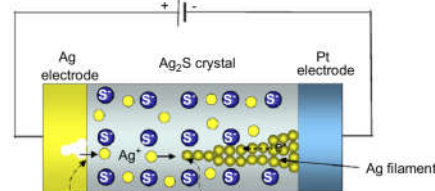


**Ag<sub>2</sub>S memristor (memory + resistor):** Ag electrode + thin Ag<sub>2</sub>S layer + electrochemically inert Me tip (e.g. PtIr or Nb).

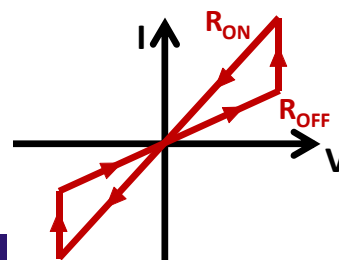
**Positive bias** (on the Ag electrode): Ag<sup>+</sup> ions move towards the Me tip → an Ag filament is grown between the two electrodes → low resistance ON state

**Negative bias:** the Ag filament is destructed → high resistance OFF state

**I(V) characteristics:** linear resistive behavior at low bias, switching to ON/OFF state above a positive/negative threshold → ideal for memory operation




K. Terabe *et al.*, *Adv. Mater* 8, 536 (2007).



Resistive Random Access Memory (ReRAM)

### Requirements against *real* ReRAM devices



- Write/erase voltage level: < 2 Volt
- Write/erase times: < 100 ns
- Read-out voltage level: < 1 Volt
- Read-out current level: ~ 0.001 – 1 mA
- OFF to ON resistance ratio > 2
- OFF state resistances < 100 kΩ

- Endurance > 10<sup>7</sup> writing cycles
- Retention times > 10 years
- Non-volatility also during read-out operations R. Waser *et al.*, *Adv. Mat.* **21**, 2632 (2009).  
J. J. Yang *et al.*, *Nat. Nanotech.* **8**, 13 (2013).


  

- CMOS competitive scaling
- CMOS compatible material systems and technology


A real resistive memory device must comply to ALL of the above requirements

A highly non-linear voltage response function is essential


### The future of mass storage media



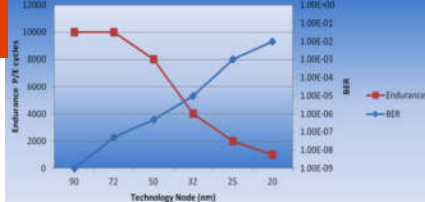
Data created worldwide: >10<sup>18</sup> byte/day  
altogether: >10<sup>22</sup> byte





**Crossbar Resistive Memory:**  
The Future Technology for NAND Flash






**FLASH memory performance**










Characteristics	FLASH memory	Crossbar ReRAM
Technology Scalability	Performance degradation below 25nm	<5nm
Program Performance	7MB/sec	140MB/sec
Asynchronous (XIP) Read	.04MB/sec	17MB/sec
Program Energy/Cell	1360pJ/cell	64pJ/cell
Endurance	3K cycles	1E6
Retention	1-3 years	20yr



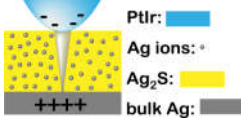



Further possibility: neuromorphic computing

### Our measurement techniques

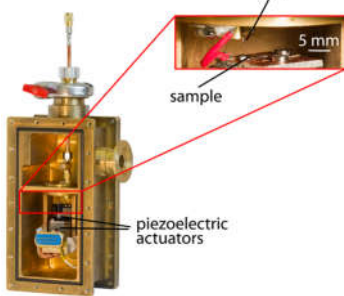
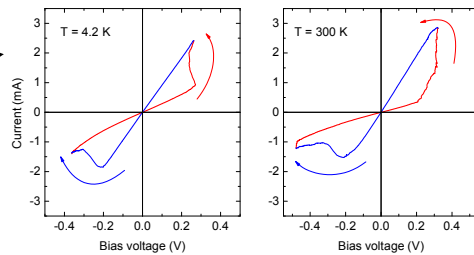
**Preparation:**  
Ag thin films  
sulfurization in HV at T=60 °C



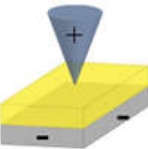
**Thick Ag<sub>2</sub>S layers:**  
semiconducting OFF state  
does not operate at T=4.2 K  
large OFF state resistance (> MOhm)

**Thin Ag<sub>2</sub>S layers (<30 nm):**  
metallic behavior in both states  
even at T=4.2 K  
optimal R<sub>ON</sub> and R<sub>OFF</sub> for high speed operation

The junction is established in a Custom designed STM

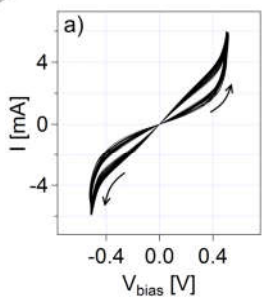
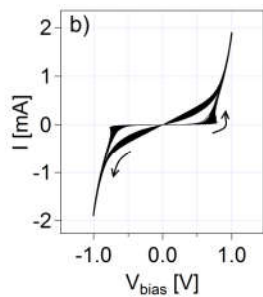
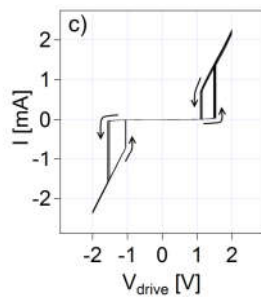



### Nb<sub>2</sub>O<sub>5</sub> memristors



PtIr tip  
Nb<sub>2</sub>O<sub>5</sub>  
Nb film

Industry-friendly material, already used in SMD capacitors  
Oxygen ions move due to the electric field.  
Regions with oxygen deficit are conducting.  
Both bipolar and unipolar resistive switching is observed.

- Highly nonlinear intrinsic I(V) characteristics: the Nb<sub>2</sub>O<sub>5</sub> memristor can be its own selector.
- Bipolar characteristics involving metallic states: fast switching
- Unipolar characteristics: high resistance at low bias in both states, avoiding sneak-path currents during read-out

